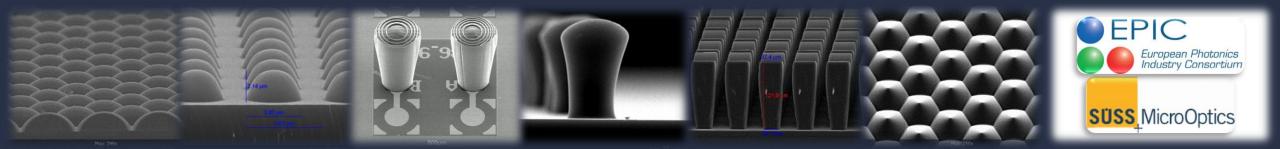
## Mater-splites foldefith on icontigatical interconnects

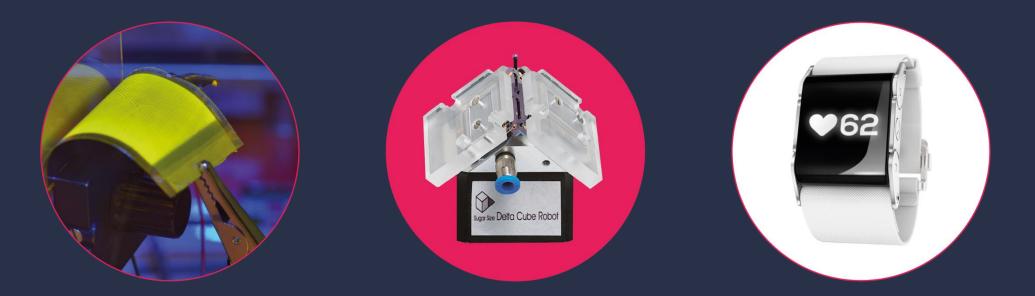
Dr. Rolando Ferrini

EPIC Meeting on Wafer Level Optics – SÜSS MicroOptics (Neuchâtel), 07-08.11.2019





## **Our mission**



Development and transfer of world-class (micro-)technologies to the industrial sector – in Switzerland, as a priority – in order to reinforce its competitive advantage.

Cooperation agreements with established companies

• Encouraging the creation of start-ups





## **CSEM** at a glance







## Close to industry, leveraging Swiss academic research







## Outline

• Wafer-scale micro-optical components : folded interconnects

• High & Low refractive index materials for UV imprint

• Freeform micro-optics



## Wafer-scale micro-optical component Folded interconnects

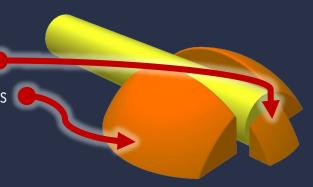
#### **Current solutions**

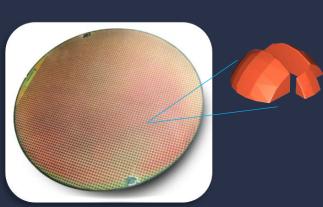
- Optical connectivity is based principally on collinear solutions
- Folded connectivity is manly done with additional components, such as parabolic mirrors, optical benches, lens mirror systems etc.

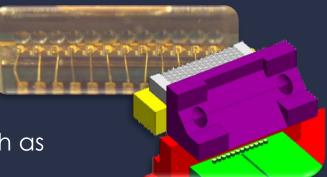
#### Our solution

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- Operational for all standard telecom optical fibers (SM & MM, 850-1650nm)
- Integrated micro-optical component:
  - Light bending ---> TIR (Total Internal Reflection)
  - Fiber coupling ---> Self-alignment micro-structures
- Wafer-scale compatible

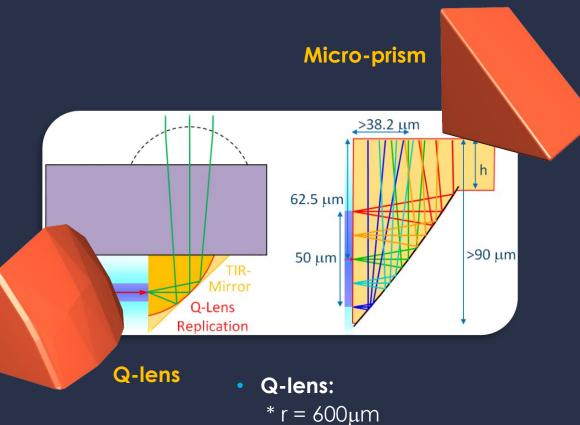








# Wafer-scale micro-optical components Design & Fabrication



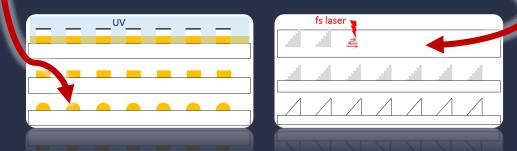
\* r = 780µm

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Micro-prism:
 \* α = 45 deg; h= 80μm

• Master origination

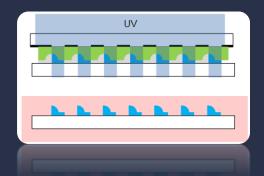
Q-lens: Wafer scale reflow (spherical only) Prism: Laser micro-fabrication (FEMTOprint©)



Mould tool on structured mask



• Lens replication and alignment structures Single process step





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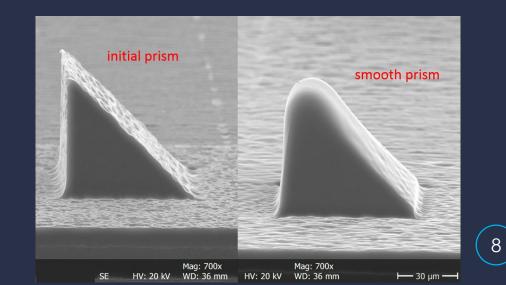
## Wafer-scale micro-optical components Fabricated folded interconnects

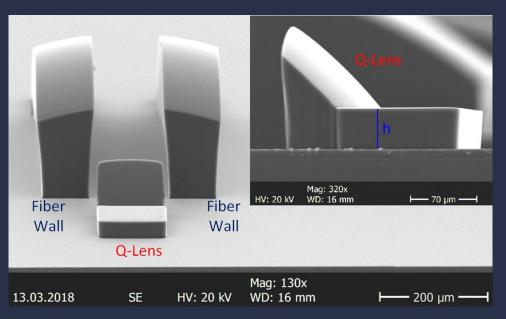
- Replication of Micro-prisms
  - o without smoothened master → rough surface
  - o with smoothened master → good surface / rounded edges

Commercial micro-prism as master benchmark

• **Replications of Q-lens** Nice surface & edges also for the alignment fiber walls







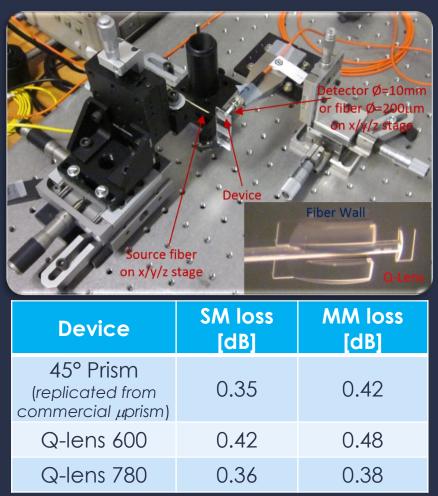
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#### Wafer-scale micro-optical components



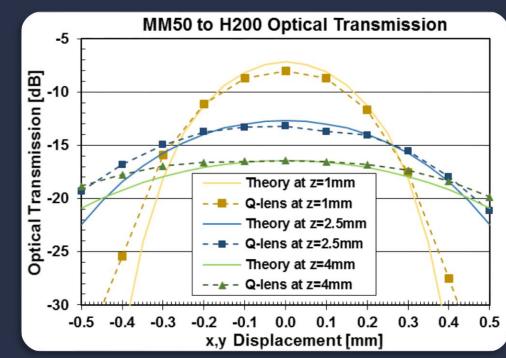
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## Folded interconnects: Optical losses & Mode profile



• Optical losses below 0.5 dB

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Results of Q-lens (r=780 µm) with MM as input fiber at different z-distances in comparison to simulations

 The optical mode profile and the angular directivity are well maintained

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## Wafer-scale micro-optical components Perspectives

- Innovative compact 90° optical interconnect using TIR based Q-lenses or micro-prisms
  - Packaging: self-aligned fiber to chip (VCSEL, Photodiodes)
  - Array structures: ribbon fibers
  - Angled fiber to fiber couplers: backplane connector with enlarged alignment tolerances
  - Integrated couplers: coupling to planar waveguides using grating couplers
- Fabrication by wafer-scale UV-imprint
- Losses as low as 0.34 dB while maintaining the optical profile
- Integrated fiber self-alignment structures



This solution will facilitate chip integration & packaging of electro-optical components (LED, VCSELs, Photodetectors, PICs etc.) to standard glass fibers

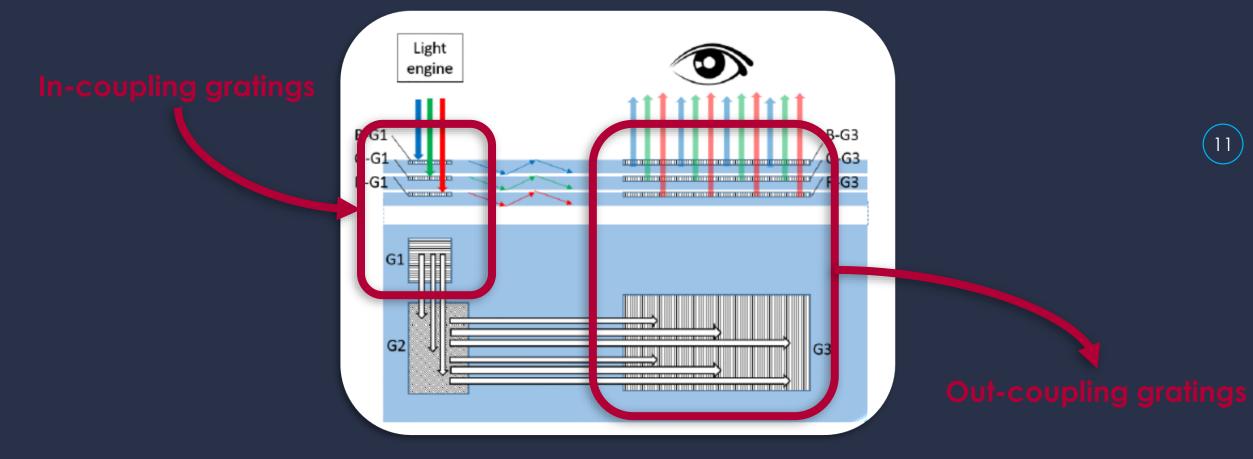
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High & Low refractive index materials for UV imprint The quest for new UV imprinting materials : Application pull

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Diffractive WGs for AR : 2D exit pupil expansion  $\rightarrow$  RI > 1.78 to enlarge the FOV



High & Low refractive index materials for UV imprint High refractive index (HRI) imprintable materials

## Approach 1

- HRI nanoparticle doping (SiO<sub>2</sub>, TiO<sub>2</sub>, ZrO<sub>2</sub>, etc.) of photoresist (polymer) or sol-gel material (inorg.-org. hybrid polymer) for UV imprint
- Applicable to both micro- & nano-imprint

## Approach 2

- UV imprint of HRI hybrid sol-gel material followed by calcination
- Applicable <u>only</u> to nano-imprint

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High & Low refractive index materials for UV imprint HRI nanoparticle doping of photoresists for UV imprint

**Approach 1** 

- **HRI nanoparticle doping** (SiO<sub>2</sub>, TiO<sub>2</sub>, ZrO<sub>2</sub>, etc.) of **photoresist** (polymer) for UV imprint
- Applicable to both micro- & nano-imprint

Refractive index measured by ellipsometry

ZrO <sub>2</sub> nano-particle loading	Fit refractive index @ $\lambda$ = 600nm
2:1	1.68
3:1	1.75

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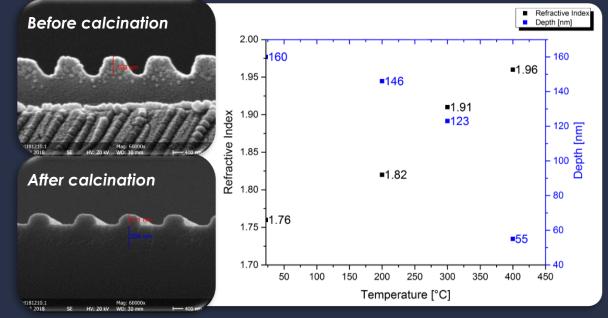
High & Low refractive index materials for UV imprint HRI hybrid sol-gel materials for UV imprint

Approach 2

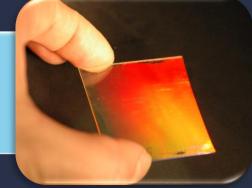
- UV imprint of HRI hybrid sol-gel material followed by calcination
- Applicable only to nano-imprint

#### Refractive index measured by ellipsometry

Calcination temperature	Fit refractive index @ $\lambda$ = 600nm
RT	1.76
200°C	1.82
300°C	1.91
400°C	1.96







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## High & Low refractive index materials for UV imprint HRI materials for AR WG couplers: In-coupling gratings

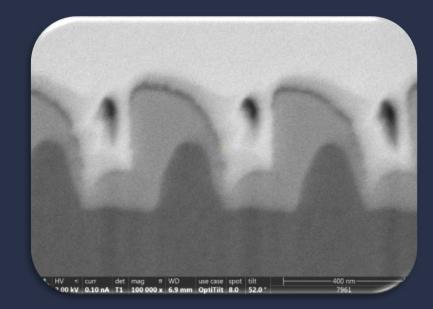
• UV nanoimprint of photoresist doped with HRI nanoparticles  $\rightarrow$  RI = 1.7

• Coating with (very) high refractive index material (> 2.0) at oblique incidence

• At  $\lambda$  = 460nm

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- $\circ$  average in-coupling efficiency = 37%
- $\circ$  incidence angle = +/- 18°
- o unpolarized light

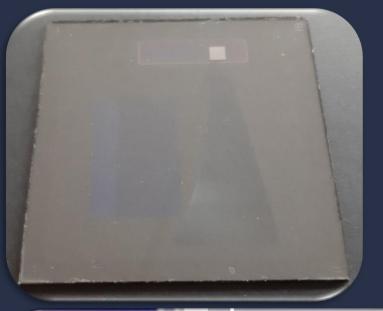


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## High & Low refractive index materials for UV imprint HRI materials for AR WG couplers : Out-coupling gratings

 Approach 1 (HRI nanoparticle doping): large light scattering after propagation in the waveguide (losses, reduced image contrast)

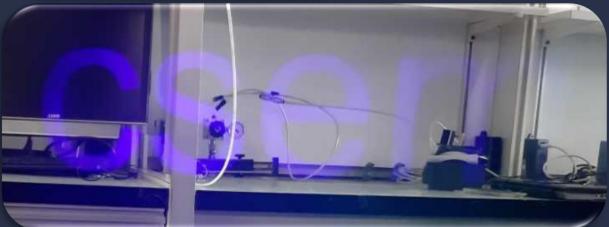


Diffractive waveguide prototype

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• Approach 2 (HRI hybrid sol-gel material): reduced surface roughness, lower light scattering, higher refractive index



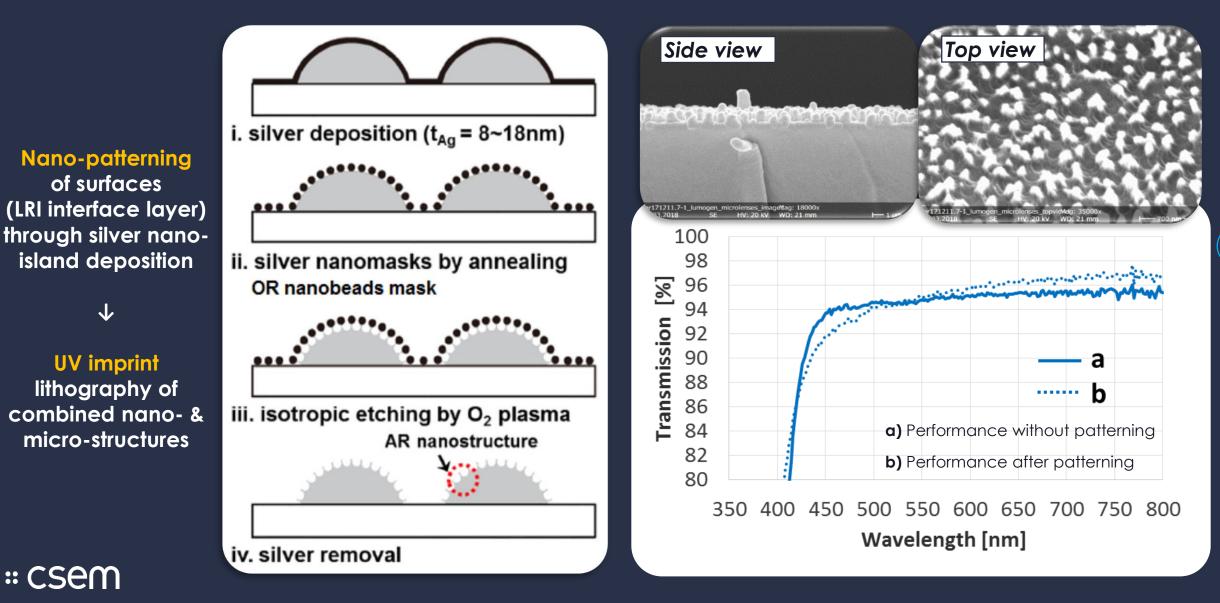
Test image outcoupled from waveguide

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#### High & Low refractive index materials for UV imprint

## Low refractive index (LRI) nano-patterned interfaces



### Freeform micro-optics Future perspectives

• Growing demand for UV imprinted nano-/micro-optical components

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- Growing demand for freeform micro-optics
  - Micro-optical surfaces with **no restrictions on symmetry**

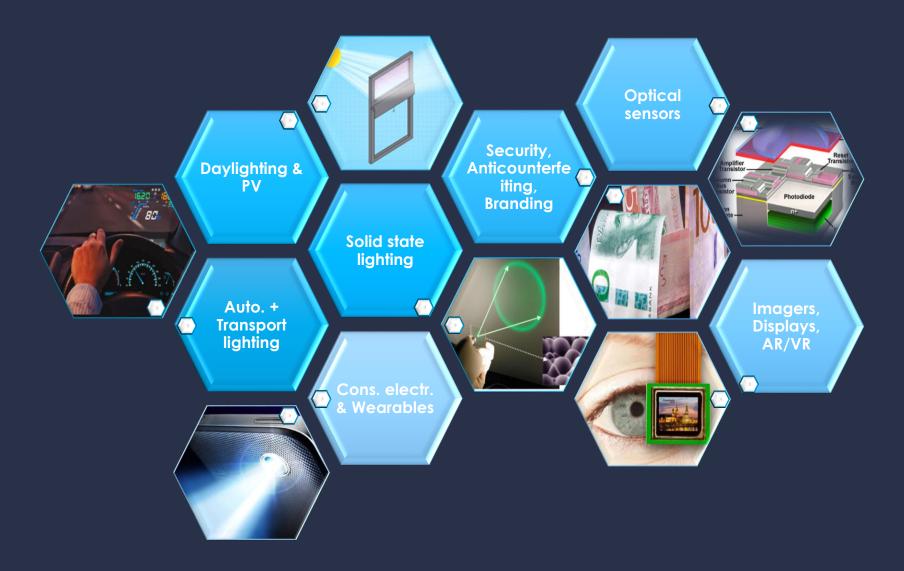
- The additional degrees of freedom enable optimum lens design and hence
  - Aberration correction (imaging)
  - Non-symmetrical light distributions (non-imaging)
  - $_{\circ}$  Fewer and/or smaller optical components  $\rightarrow$  Miniaturization & Integration



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(19)

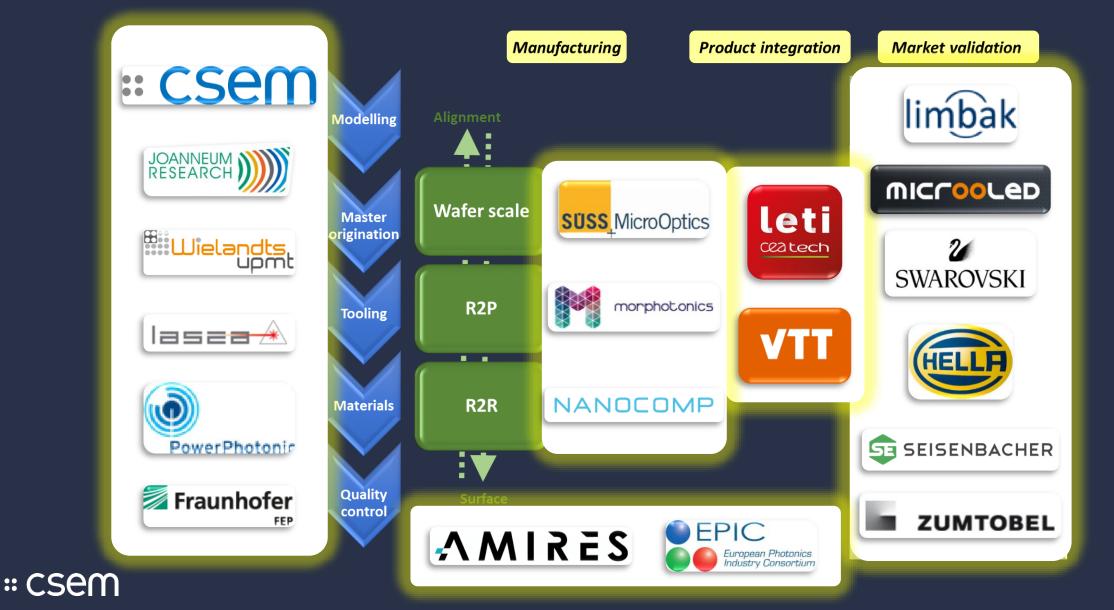
# Freeform micro-optics Application cases



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#### Freeform micro-optics

## Complex manufacturing eco-system







## PHABUL $\mu$ OS: Pilot line for free-form micro-optics

• 19 partners: Research & Technology Organizations (RTOs) and Companies along the manufacturing value chain Who • European pilot line for the manufacturing of freeform micro-optical components with a clear roadmap for high volume production in Europe at competitive cost What • 3 UV replication technologies (wafer scale, R2P, R2R) • Accelerated innovation cycles from prototypes to large volume production Boost in new product developments A manufacturing one-stop shop for SMEs up to LMEs How • An **European ecosystem** for free form micro-optics



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## Freeform micro-optics

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## PHABULµOS: The consortium









January 1<sup>st</sup>, 2020



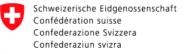
Photonics Public Private Partnership www.photonics21.org



## Thank you for your attention!

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Innosuisse - Swiss Innovation Agency





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## Micro-opticsisyour attention!

# PHABULOUS

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## This presentation was presented at EPIC Meeting on Wafer Level Optics 2019

